



發明名稱

(以下內容一頁為限，不可揭露關鍵技術內容；填表完成後請刪除此行)

發明人：呂宗昕 教授

單位：國立臺灣大學 化工學系/研究所

簡歷：(可列出相關連結，例如系所、研究室網頁)

本實驗室研究領域乃在於奈米技術、光電材料、電子陶瓷、CIGS 太陽能電池、螢光粉。目前研究題目包括：

奈米電子及光電材料之製備及改質

電子及光電元件薄膜製程

電子及光電材料分析及元件設計

<http://homepage.ntu.edu.tw/~d01524001/index.html>

請放任一代表照片

(不可揭露技術內容)

市場及需求：

化學機械研磨 (Chemical-Mechanical Polishing, CMP)

技術摘要(含成果)：

本技術可於低溫下，利用水熱法合成奈米級小粒徑的圓球狀氧化鈰粉體，並且具有粒徑分佈均勻以及分散性良好等優點。相較於市面上非球狀且粒徑較大之氧化鈰粉體，透過本技術合成之氧化鈰粉體，可避免研磨對象表面的損傷，有效進行研磨。

優勢：

透過此技術，能將合成氧化鈰粉體之所需溫度大幅降低，合成粒徑分佈均勻、分散性良好的小粒徑圓球狀氧化鈰粉體，有利於降低製造成本，以及避免研磨時造成研磨物體表面受損。

競爭產品：

專利現況：

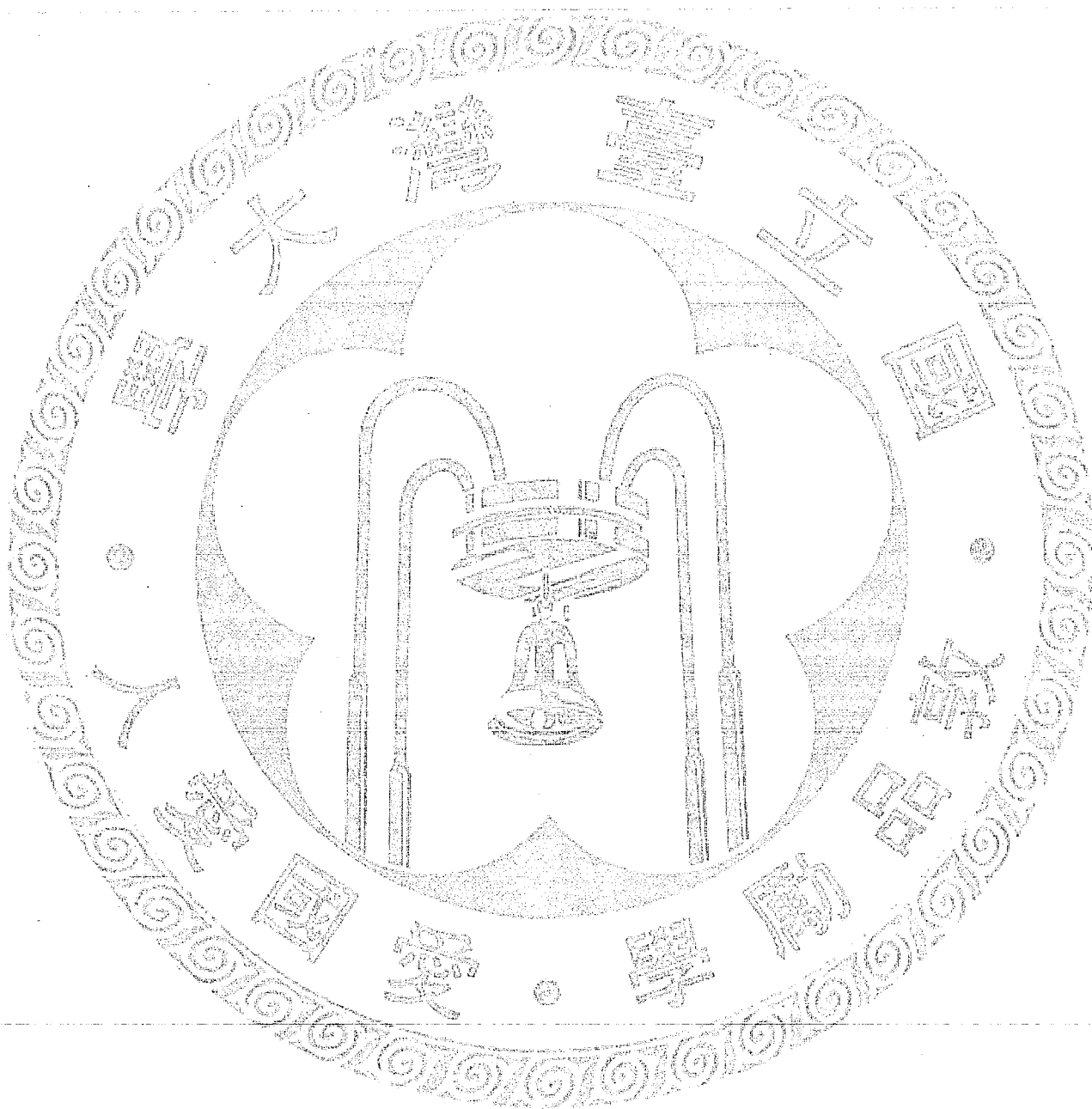
- (1) 本技術已有相關專利 (中華民國專利申請號: XXXX; 美國專利證號: XXX)。
- (2) 本研究團隊具有數十年研究經驗...
- (3) 其他...

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Title of Invention

(Below is limited to 1-page only; be careful not to disclose vital technology content. Please delete these words when the document is finished)

PI : Prof. Chung-Hsin Lu

Department of Chemical Engineering, National Taiwan U.

Experience:

The research fields in our laboratory are nano technology, photoelectric materials, electronic ceramics, CIGS solar cell, and phosphor. The current topics include:

Synthesis and Modification of Nano Electronic and Photoelectric Materials

Process of Films of Electronic and Photoelectric Device

Analysis and Designation of Electronic and Photoelectric Device

An interesting **photo** related to your technology
(be careful not to disclose key technology)

Market Needs:

Chemical-Mechanical Polishing, CMP

Our Technology:

By this technology, we can synthesize nano scale spherical CeO₂ with small size, uniform distribution and good disperion. Compare to the larger and non-spherical CeO₂ on the market, CeO₂ synthesized by this technology can avoid the surface damage of the object and polish the object effectively.

Strength:

By this technology, we can significantly decrease the temperature of CeO₂ synthesis and synthesize CeO₂ with uniform size distribution, good dispersion, small size, and spherical shaped. These characteristics are beneficial to reduce the cost and avoid the surface damage of the object while polishing.

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Competing Products:

Intellectual Properties:

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